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# Chromatic Change in Copper Oxide Layers Irradiated with Low Energy Ions

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**Abstract:** The color of a thin copper oxide layer formed on a copper plate was transformed from reddish-brown into blue-purple by irradiation with 5 keV Ar $^+$  ions to a fluence as low as  $1 \times 10^{15}$  Ar $^+$  cm $^-$ 2. In the unirradiated copper oxide layer, the copper valence state of Cu $^2$  $^+$  as well as Cu $^+$  and/or Cu $^0$  was included as indicated by the presence of a shake-up satellite line in a photoemission spectrum. While for the irradiated one, the satellite line decreased in intensity, indicating that irradiation resulted in the reduction from Cu $^2$  $^+$  to Cu $^+$  and/or Cu $^0$ . Furthermore, nuclear reaction analysis using a  $^{16}$ O(d, p) $^{17}$ O reaction with 0.85 MeV deuterons revealed a significant loss of oxygen (5×10 $^{15}$  O atoms cm $^{-2}$ ) in the irradiated layer. Thus, the chromatic change observed in the present work originated in the irradiation-induced reduction of a copper oxide.

Keywords: ion beam; copper oxide; chromatic change; photoemission spectrum; beam viewer

## 1. Introduction

On ion beam experiments including materials analysis and modification with ion beams, a beam monitoring system is installed in the sample chamber to monitor the beam position and uniformity in the beam spot. Most of the beam monitor consists of a fluorescent plate, enabling real time visualization of a beam spot on the plate. A SiO2 plate, for example, has been used for beam monitoring because of strong emission [1-5] in the visible range when irradiated with MeV-ion beams. A Cr-doped Al<sub>2</sub>O<sub>3</sub> (e.g., AF995R, Desmarquest) is also suitable for beam profiling [6,7] for ion beams with energies larger than several hundred keV. The aforementioned materials are insulator and therefore electric charging takes places on the fluorescent plate irradiated with ion beams, resulting in deflection of ion beams in the vicinity of the fluorescent plate if their acceleration voltage is comparable to the charged potential of a few tens kilovolts [8]. This means that the fluorescent point would be different from the real position, and further the fluorescent point would not appear at all in the case of low energy ion beams with < 10 keV. In addition to the fluorescent materials, phosphors such as ZnS based materials [9–11], which have been widely used for screens of a cathode-ray tube, are applicable to beam monitoring. Other candidates of inorganic luminescent materials can be found in the literature [12]. Powders of such materials, mixed with a conducting paste and deposited onto a conducting plate, are candidate for ion beam monitoring materials. However, such powders cost very high, but their lifetimes are very short because radiation damage causes degradation of lightemitting efficiency. It is, therefore, not easy to view a beam spot of a low energy ion beam with energy of several keV on real-time.

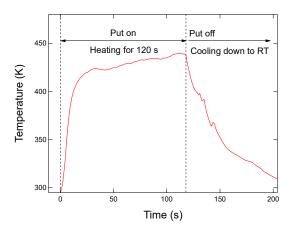
On the other hand, non-real time beam monitoring can be conducted by the color change of materials irradiated with ion beams. A polyimide film is, for example, widely used to check both the position and uniformity of an ion beam, because blackening due to graphitization [13–15] occurs when the film is irradiated with ion beams. A polyimide film

is, however, non-conducting and is unapplicable to the beam viewer for low energy ion beams with energies of several keV. The favorable beam viewer for low energy ion beams should be composed of electrically conducting materials. A metallic copper plate, even if a thin upper layer of copper oxide is present, is good conducting material. The color of the copper plate covered with thin oxide is reddish-brown, largely different from polished metallic copper. The present authors made attempt to fabricate a beam viewer in which the appearance of a beam spot turns shiny due to removal of the oxide layer by physical sputtering. In the irradiation apparatus with base pressure of ~2 ×  $10^{-4}$  Pa, the shiny beam spot could be clearly recognized after irradiation with 5 keV Ar+ ions to a fluence of 1 ×  $10^{15}$  Ar+ cm-2. Surprisingly, in the other irradiation equipment with base pressure of ~2 ×  $10^{-6}$  Pa, the color of the beam spot turned blue-purple after irradiation under the same conditions above. In the present work, the chromatic change observed in the irradiation equipment with such a high vacuum is examined to fabricate a new type of beam viewer for low energy ion beams.

#### 2. Materials and Methods

Oxygen-free copper plates of  $10 \times 10 \times 1$  mm³ (purity 99.99 %) were supplied from NILACO, Japan. The Cu plate was put on a laboratory hot plate setting to 473 K in ambient air for 2 min to form Cu oxide layer. The maximum temperature measured on the surface with chromel-alumel thermocouple was 440 K, somewhat lower than the setting temperature of 473 K, as recorded in Fig. 1. The color of heat-treated Cu plate was reddish-brown. The samples were irradiated with 5 keV-Ar+ ions up to a fluence of  $1 \times 10^{15}$  cm-2 using a 5 kV-ion gun installed in a vacuum chamber with a base pressure of  $2 \times 10^{-6}$  Pa.

X-ray photoelectron spectroscopy (XPS) using Mg K $\alpha$  radiation (hv = 1253.6 eV) was performed with a JEOL 9010 X-ray photoelectron spectrometer (JEOL, Japan) to analyze chemical states of Cu before and after the irradiation. Rutherford backscattering spectrometry (RBS) and nuclear reaction analysis (NRA) using the  $^{16}$ O(d, p) $^{17}$ O reaction were conducted for chemical composition analysis with 2 MeV He ions and 0.85 MeV deuterons, respectively, produced from the Van de Graaff accelerator of Hiroshima University. The standard sample for the NRA was a SiO<sub>2</sub> layer formed on a Si wafer (SiO<sub>2</sub>/Si), which contains  $5.8 \times 10^{17}$  O atoms·cm<sup>-2</sup> determined by RBS.



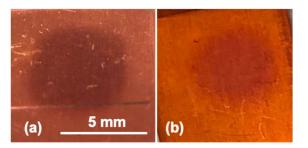
**Figure 1.** Temperature measured on the sample surface with chromel-alumel thermocouple during oxidation.

### 3. Results and Discussions

Figure 2 (a) shows a photograph of the sample surface irradiated with  $Ar^+$  ions to a fluence of  $1\times 10^{15}$  cm<sup>-2</sup> using a 5 kV ion gun. The color of the sample changed from reddish brown to blue-purple at an irradiation spot. This chromatic change started at the fluence as low as  $10^{14}$  cm<sup>-2</sup>. On the sample surface irradiated to a fluence of  $10^{14}$  cm<sup>-2</sup>, the color of

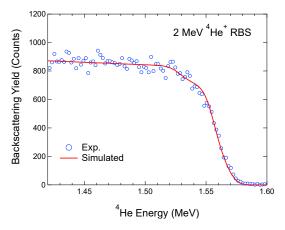
the edge at the beam spot is not clear as can be seen in Fig. 2 (b), indicating that the border between irradiated and unirradiated areas is not so abrupt. Thus, the uniformity of a beam intensity inside the beam spot can be estimated by the uniformity of color.

Figure 2. Photographs of the surface of samples irradiated with 5 keV-Ar+ ions to fluences of 1 ×



 $10^{15} \text{ cm}^{-2}$  (a) and  $1 \times 10^{14} \text{ cm}^{-2}$  (b).

The mechanism of the observed chromatic change is discussed below, along with RBS, NRA and XPS data. Figure 3 shows the backscattering spectrum of the Cu oxide layer formed on a Cu plate before irradiation. The chemical composition and thickness of the oxide layer was estimated to be  $\text{CuO}_{0.4}$  and  $1.9 \times 10^{17}$   $\text{CuO}_{0.4}$  cm<sup>-2</sup>, respectively, by fitting a simulation spectrum to experimental data, where the program SIMNRA 6.06 [16] was used to obtain the simulation spectrum. The chemical composition  $\text{CuO}_{0.4}$  indicates that the oxide layer contains the mixture of metallic copper and copper oxides.



**Figure 3.** RBS spectrum of the as-prepared sample (blue open circles). A simulated spectrum (red solid line) is also shown.

Figure 4 presents the NRA spectra of the sample with and without irradiation. Peaks located around channel number of 260 correspond to protons emitted by the  $^{16}\text{O}(d, p)^{17}\text{O}$  reaction. The peak intensities are  $2.15 \times 10^3$  and  $2.01 \times 10^3$  counts for the unirradiated and irradiated samples, respectively. The oxygen content in the irradiated sample was determined to be  $7.1 \times 10^{16}$  O atoms·cm<sup>-2</sup> by the SiO<sub>2</sub>/Si standard sample, smaller by ~10 % than that in the unirradiated sample ( $7.6 \times 10^{16}$  O atoms·cm<sup>-2</sup>). Thus, oxygen atoms were found to be released from the CuO<sub>0.4</sub> layer by the irradiation with 5 keV-Ar<sup>+</sup> ions to a fluence of  $1 \times 10^{15}$  cm<sup>-2</sup>. The SRIM simulation [17] predicts the sputtering yield of O in CuO<sub>0.4</sub> to be 4.9 O atoms·cm<sup>-2</sup>, which means that the sputtered O atoms will be approximately  $5 \times 10^{15}$  O atoms·cm<sup>-2</sup>, corresponding to a difference in the oxygen contents between the unirradiated and irradiated samples. The NRA results and the SRIM calculation suggest that the release of O atoms originates in physical sputtering. In the sputtering process of CuO<sub>0.4</sub> bombarded with 5 keV-Ar<sup>+</sup> ions, approximately  $1.4 \times 10^{15}$  Cu atoms·cm<sup>-2</sup> as calculated by

the SRIM will be desorbed, leading to the change in chemical composition from  $CuO_{0.4}$  to  $CuO_{0.38}$  in the layer.

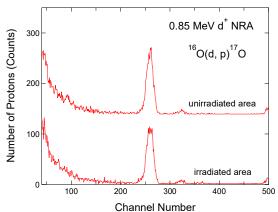


Figure 4. NRA spectra of the unirradiated and irradiated areas in the sample irradiated with 5 keV-Ar+ ions to a fluence of  $1 \times 10^{15}$  cm<sup>-2</sup>.

Figure 5 shows XPS Cu 2p core level photoemission spectra (PS) of the  $CuO_{0.4}$  layer with and without irradiation. As can be seen in Fig. 5, a broad shake-up satellite line due to the charge transfer [18,19] appears in the binding energy (BE) region from 937 to 941 eV of PS for the unirradiated sample and decreases in intensity after irradiation. More quantitatively, the intensity ratio of the satellite to the main line at BE of 932.4 eV was 0.16 and 0.10 for the unirradiated and irradiated samples, respectively. These results indicate that the unirradiated sample includes the copper valence state  $Cu^{2+}$  and it is transformed into  $Cu^{+}$  and/or  $Cu^{0}$  ( $Cu^{+}/Cu^{0}$ ) by irradiation. Thus the 5 keV-Ar<sup>+</sup> irradiation reduces  $Cu^{2+}$  to  $Cu^{+}/Cu^{0}$ . The irradiation-induced reduction observed in the present work can be seen in the change in shape of  $Cu^{-}$  2p<sub>3/2</sub> lines before and after irradiation.

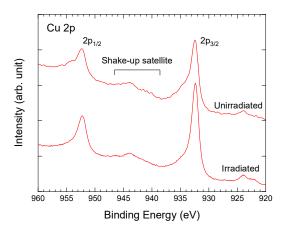
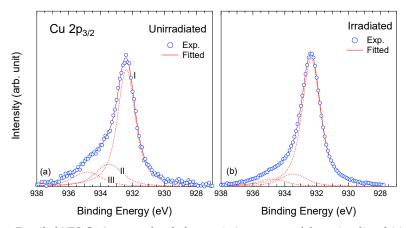


Figure 5. XPS Cu 2p core level photoemission spectra of the unirradiated and irradiated areas in the sample irradiated with 5 keV-Ar+ ions to a fluence of  $1 \times 10^{15}$  cm<sup>-2</sup>.

Figures 6 (a) and (b) depicts Cu  $2p_{3/2}$  lines for the samples before and after irradiation, respectively. Each spectral line consists of three components denoted by I, II and III. The lines, after background subtraction by the Shirly method [20], were decomposed by three Voigt functions using a curve fitting procedure. The component I located at BE of 932.4 eV is assigned to be Cu and/or Cu<sub>2</sub>O. The BE of Cu (932.6 eV) [21–23] is very closed to that of Cu<sub>2</sub>O (932.5 eV) [24–27], therefore the component I cannot be further decomposed by a curve fitting. The components II and III located at BE of 933.6 eV and 934.8 correspond to

CuO [27–30] and Cu(OH) $_2$  [27,31], respectively. The fractions of each component obtained by the curve fitting are summarized in Table 1 for the samples with and without irradiation. The fractions corresponding to copper valence state Cu $^{2+}$  (CuO and Cu(OH) $_2$ ) decrease, while the fraction of Cu $^+$ /Cu $^0$  (Cu $_2$ O/Cu) increases by irradiation, indicating that the Ar $^+$  irradiation reduces Cu $^{2+}$  to Cu $^+$ /Cu $^0$ . This is consistent with the result deduced from the decrease in intensity of shake-up satellite line as described above.



**Figure 6.** Detailed XPS Cu  $2p_{3/2}$  core level photoemission spectra of the unirradiated (a) and irradiated (b) areas in the sample irradiated with 5 keV-Ar+ ions to a fluence of  $1 \times 10^{15}$  cm<sup>-2</sup>. Each spectrum was decomposed into three components denoted by I, II and III.

The concentration ratio of Cu<sub>2</sub>O to Cu can be indirectly determined by the atomic ratio O/Cu of analyzing layer using the fractions of three components. Of course, the O/Cu can be calculated by the intensity ratio of O 1s to Cu 2p PS lines. However, it is impossible to accurately determine the atomic ratio O/Cu because of the presence of adventitious carbon contamination that includes oxygen atoms in the outermost layer. Therefore, the atomic ratio O/Cu in the analyzing layer is assumed to be 0.4 that is determined by RBS, resulting in the concentration ratio Cu<sub>2</sub>O/Cu of 8.2/65.7 for the sample without irradiation. These values are presented with parenthesis in Table 1. For the sample with irradiation, the atomic ratio O/Cu in the analyzing layer is definitely different from that in the oxide layer, and thus, the composition CuOo.38 determined by the combination of RBS and NRA cannot be used to calculate the fraction of Cu<sub>2</sub>O/Cu. Therefore, the fraction of metallic copper is assumed to be unchanged after irradiation. In fact, Panzner et al. [32] demonstrated that the oxide CuO was reduced to Cu2O, while the oxide Cu2O was much more stable and no more reduction to Cu occurred under sputtering with 3-5 keV Art to a low fluence. Then the concentration ratio Cu<sub>2</sub>O/Cu is calculated to be 28.4/65.7 for the sample with irradiation. These values are also presented inside parenthesis in Table 1.

**Table 1.** Compositions of Cu, Cu<sub>2</sub>O, CuO and Cu(OH)<sub>2</sub> determined by Cu  $2p_{3/2}$  PS lines for the unirradiated and irradiated samples.

Samples	Compositions (%)			
	Cu	Cu <sub>2</sub> O	CuO	Cu(OH)2
Unirradiated	73.8		16.5	0.7
	$(65.7)^1$	$(8.1)^1$	16.5	9.7
Irradiated	94.1			0.4
	$(65.7)^1$	$(28.4)^1$	5.5	0.4

 $<sup>^{1}</sup>$  These values were obtained by the assumption that the composition of the analyzing layer was  $CuO_{0.4}$  before irradiation and the fraction of Cu was unchanged after irradiation.

As described above, XPS analysis reveals that the 5 keV-Ar $^{+}$  irradiation reduces  $Cu^{2+}$  to  $Cu^{+}/Cu^{0}$  in the cuprate. This result is consistent with the previous studies that CuO thin films were transformed into  $Cu_{2}O$  by ion irradiation [32,33]. Next, the relationship between the reduction and the chromatic change is discussed.

It is well known that the color of cuprous oxide (Cu<sub>2</sub>O) powder is red. In addition, Cu<sub>2</sub>O in the form of both thin film [34,35] and nanoparticle [36,36] would be reddish considering their optical absorption spectra. On the other hand, the color of the irradiated layer was found to be blue-purple, different from the color of pure Cu<sub>2</sub>O. Fredj and Burleigh [38] showed that the color of a copper oxide layer in which Cu<sub>2</sub>O is primarily included varied from bare copper color to green depending on its thickness. The color of the oxide with thickness of ~20 nm was found to be violet blue, similar to the color observed on the irradiated sample in this work. It is, therefore, concluded that the chromatic change observed originates in the presence of a very thin oxide layer that mainly consists of Cu<sub>2</sub>O produced by the irradiation-induced reduction from CuO and Cu(OH)<sub>2</sub>.

As mentioned in Introduction, the beam spot in the sample irradiated with 5 keV-Artions using the other machine turned bare copper color due to the removal of an oxide layer by sputtering, different from the present work. The reason for this difference is unknown but may result from the initial composition of the oxide layer. Further studies are needed to clarify the mechanism underlying the irradiation-induced chromatic change in copper oxide layers and to create a new type of beam viewer for low energy ion beams. Such investigations are now in progress using copper oxides with various compositions.

#### 4. Conclusions

The color of a thin copper oxide layer formed on a copper plate turned from reddish-brown to blue-purple by irradiation with 5 keV Ar+ ions to a fluence of  $1\times10^{15}$  Ar+ cm<sup>-2</sup>. Nuclear reaction analysis revealed that a significant amount of oxygen ( $5\times10^{15}$  O atoms·cm<sup>-2</sup>) was released from the irradiated layer. The reduction of cupric oxide (CuO) to cuprous oxide (Cu<sub>2</sub>O) occurred in the layer after the irradiation as confirmed by the decrease in intensity of a shake-up satellite line as well as the change in the shape of a Cu  $2p_{3/2}$  line in photoemission spectra. The reduction leads to the compositional change in the mixture of Cu/Cu<sub>2</sub>O/CuO, which results in the chromatic change.

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